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- 44. (Amended) A substrate comprising a surface with at least one electrophilic or nucleophilic functional group attached thereto, said substrate having a coating positioned thereon, the coating comprising an amorphous chemically crosslinked material comprising elements selected from the group consisting of (1) M, O, C, H, and N; wherein M is a metal selected from the group consisting of silicon, titanium, tantalum, germanium, boron, zirconium, aluminum, hafnium, and yttrium; (2) M, O, H, and N wherein M is defined above; and (3) O, C, H, a and N and wherein the chemically crosslinked material is terminated with the at least one electrophilic or nucleophilic functional group.
- 45. (Amended) A substrate comprising a surface with at least one electrophilic or nucleophilic functional group attached thereto, said substrate having a coating positioned thereon, the coating comprising an amorphous chemically crosslinked material comprising elements selected from the group consisting of (1) M, O, C, H, and N; wherein M is a metal selected from the group consisting of silicon, titanium, tantalum, germanium, boron, zirconium, aluminum, hafnium, and yttrium; (2) M, O, H, and N wherein M is defined above; (3) O, C, H, a and N; and (4) M or C, and one of O, H, or N; and wherein the chemically crosslinked material is terminated with the at least one electrophilic or nucleophilic functional group.
- 46. (Amended) A substrate comprising a surface with at least one electrophilic or nucleophilic functional group attached thereto, said substrate having a coating positioned thereon, the coating comprising an amorphous chemically crosslinked material comprising Si, C, and H deposited in a PECVD process with a tetra methyl silane (Si(CH<sub>3</sub>)<sub>4</sub>) precursor and wherein the chemically crosslinked material is terminated with the at least one electrophilic or nucleophilic functional group.
- 47. (Amended) A substrate comprising a surface with at least one electrophilic or nucleophilic functional group attached thereto, said substrate having a coating positioned thereon, the coating comprising an amorphous chemically crosslinked material comprising elements selected from the group consisting of (1) M, O, C, H, and N; wherein M is a metal selected from the group consisting of silicon,





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titanium, tantalum, germanium, boron, zirconium, aluminum, hafnium and yttrium; (2) M, O, H, and N wherein M is defined above, (3) C; (4) O, C, H, and N; and (5) M or C, and one of O, H, or N, wherein the chemically crosslinked material is terminated with the at least one electrophilic or nucleophilic functional group and wherein the at least one electrophilic or nucleophilic functional group is deposited by a plasma treatment.

- 48. (Amended) A substrate comprising a surface with at least one electrophilic or nucleophilic functional group attached thereto, said substrate having a coating positioned thereon, the coating comprising an amorphous chemically crosslinked material comprising elements selected from the group consisting of (1) M, O, C, H, and N; wherein M is a metal selected from the group consisting of silicon, titanium, tantalum, germanium, boron, zirconium, aluminum, hafnium and yttrium; (2) M, O, H, and N wherein M is defined above, (3) C; (4) O, C, H, and N; and (5) M or C, and one of O, H, or N, wherein the chemically crosslinked material is terminated with the at least one electrophilic functional group for electrostatically attracting positively charged molecules for adsorption and electrostatically repelling negatively charged molecules for non-adsorption.
- 49. (Amended) A substrate comprising a surface with at least one electrophilic or nucleophilic functional group attached thereto, said substrate having a coating positioned thereon, the coating comprising an amorphous chemically crosslinked material comprising elements selected from the group consisting of (1) M, O, C, H, and N; wherein M is a metal selected from the group consisting of silicon, titanium, tantalum, germanium, boron, zirconium, aluminum, hafnium and yttrium; (2) M, O, H, and N wherein M is defined above, (3) C; (4) O, C, H, and N; and (5) M or C, and one of O, H, or N, wherein the chemically crosslinked material is terminated with the at least one nucleophilic functional group for electrostatically attracting negatively charged molecules for adsorption and electrostatically repelling positively charged molecules for nonadsorption.
- 50. (Amended) A substrate comprising a surface with at least one electrophilic or nucleophilic functional group attached thereto, said substrate having a





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coating positioned thereon, the coating comprising an amorphous chemically crosslinked material comprising elements selected from the group consisting of (1) M, O, C, H, and N; wherein M is a metal selected from the group consisting of silicon, titanium, tantalum, germanium, boron, zirconium, aluminum, hafnium and yttrium; (2) M, O, H, and N wherein M is defined above, (3) C; (4) O, C, H, and N; and (5) M or C, and one of O, H, or N, wherein the chemically crosslinked material is terminated with the at least one nucleophilic functional group.

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